



World Class Accreditation

The American Association for Laboratory Accreditation

# Accredited Laboratory

A2LA has accredited

## TM LABORATORIES, LLC

*Gettysburg, PA*

for technical competence in the field of

### Chemical Testing

This laboratory is accredited in accordance with the recognized International Standard ISO/IEC 17025:2005 *General Requirements for the Competence of Testing and Calibration Laboratories*. This accreditation demonstrates technical competence for a defined scope and the operation of a laboratory quality management system (*refer to joint ISO-ILAC-IAF Communiqué dated 8 January 2009*).

Presented this 20<sup>th</sup> day of July 2009.

A handwritten signature in black ink, reading "Peter Abney".

President & CEO

For the Accreditation Council

Certificate Number 3999.01

Valid to 31 July 2011



*For the tests or types of tests to which this accreditation applies, please refer to the laboratory's Chemical Scope of Accreditation.*



SCOPE OF ACCREDITATION TO ISO/IEC 17025:2005

TM LABORATORIES, LLC  
123 Main Street  
Gettysburg, PA 17320  
Ken Horn Phone: 717 334 5555

CHEMICAL

Valid To: July 31, 2011

Certificate Number: 3999.01

In recognition of the successful completion of the A2LA evaluation process, accreditation is granted to this laboratory to perform the following types of chemical analysis tests:

TEST DESCRIPTION

TEST METHOD

**Determination of Trace Metals in Ultra Pure Water (UPW)**

Measurement of TM in UPW by ICP-MS  
Measurement of Trace Metals in UPW by High Resolution ICP-MS

ICP-0007  
ICP-0013

**Determination of Trace Metals in Chemicals**

Determination of Trace Metals in Chemicals  
Direct Analysis of Trace Elements in Chemicals by High Resolution ICP-MS  
TM Analysis of Chemicals by Dilute & Shoot  
TM by Closed Evaporation  
Thiers Chambers  
Graphite Furnace Analysis (GFA) in the Chemicals Laboratory

ICP-0010  
ICP-0014  
CHM-0008  
CHM-0027  
CHM-0029  
CHM-0033

**Determination of Trace Elements on Wafers by VPD ICP-MS or GFAA**

Determination of Trace Metals on Silicon Wafer Surface by VPD  
Determination of Boron and Phosphorous on Wafers

VPD-0002  
VPD-0005

TEST DESCRIPTIONTEST METHOD**Wet Chemistry**

Determination of Dissolved Silica in UPW by Colorimetry WAT-0009  
Determination of Total Oxidizable Carbon (TOC) in UPW WAT-0020

**Determination of Trace Anions & Cations**

IC Extractable Compounds WAT-0001  
IC Analysis of Water for Organic Acids and Fluoride WAT-0007  
IC Analysis of Amines in Cleanroom Air WAT-0019  
Determination of Trace Anions & Cations in UPW by Ion Chromatography WAT-0026  
Acid & Base Anhydrides in Air WAT-0029  
IC Analysis if Anions & Cations in Air- High PPB Level WAT-0033

**Organic Analysis by Thermal Desorption (TD) GC-MS**

GC-MS Identification of Organics on Wafers ORG-0003  
Organic Contaminants in Air ORG-0004

**Organic Analysis by Thermal Desorption (TD) GC-MS**

Outgassing by TD-GC-MS ORG-0006  
Off-Line Outgassing by GC-MS ORG-0009

**Solvent Assays by GC or GC-MS**

Area % Assay for Solvents or Mixtures by Gas Chromatography ORG-0005  
Quantitative Analysis of Solvent Mixtures by GC-TCD Weight % ORG-0008  
Qualitative Analysis of Liquid Samples by GC-MS ORG-0010  
Semi Volatile Organics in Water ORG-0011  
GC-MS Identification of Organics on Wafer, ORG-0012  
ASTM "F-1982-99, Method B - Non- Breaking method"

**Determination of Particles**

Determination of Optical Particle Counts in UPW WAT-0015  
Determination of Particles by SEM-DCM WAT-0016  
Particles by Nomura WAT-0017

**Bacterial Examination of Water**

Cultured Bacteria in Water WAT-0012  
EPI Fluorescence Bacteria – Direct Count WAT-0013

**Determination of Boron and/or Phosphorous in SiO<sub>2</sub> (BPSG, BSG, PSG Films) by ICP-OES**

Determination of Boron and/or Phosphorous in SiO<sub>2</sub>  
(BPSG, BSG, PSG Films) by ICP-OES TFL-0003  
% Boron and % Phosphorous Analysis of 300mm Wafers TFL-0009  
Wafer Mapping for BPSG, PSG, BSG Films TFL-0012  
Non-Breaking Wafer Mapping of 300mm Wafers TFL-0021



TEST DESCRIPTION

TEST METHOD

**Determination of Phosphorous in SiO<sub>2</sub> (BPSG and PSG Films) by Colorimetry**

Determination of Phosphorous in SiO <sub>2</sub> (BPSG and PSG Films) by Colorimetry	TFL-0007
% Boron and % Phosphorous Analysis of 300mm Wafers	TFL-0009
Wafer Mapping for BPSG, PSG, BSG Films	TFL-0012
Non-Breaking Wafer Mapping of 300mm Wafers	TFL-0021

**On-site Sampling**

Sampling of Liquid Processing Chemicals	CHM-0032
Determination of Ti & W in Thin Films by ICP-OES	TFL-0004
Determination of Ni & Fe in Thin Films by ICP-OES	TFL-0006
Silicon Thin Film Analysis	TFL-0008
Determination of % Copper in Wafer by ICP-OES	TFL-0014
Water Sampling	WAT-0022

On the following types of materials:

Wafer, Ultra Pure Water, Chemicals and Air Analysis for the Semiconductor Industries

